

APOL-LO 3200 – run sheet

KemLab

nanyte.com/photoresists/apol-lo-3200 · last updated 2026-07-26

Thickness: 2–10 μm

Softbake: 110 °C · 60 s · hotplate

Post-exposure bake: 110 °C · 60 s

Develop: Developer 0.26N TMAH